# Monthly LabAdviser/Process2Share update: 20/3 2015

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| Updated Subject  | Contributor | Link to the updated pages |
| **XPS**Carbon contamination | **Kasper Reck-Nielsen @danchip** | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Characterization/XPS#Carbon_Contamination> |
| **AOE**SiO2 etching with CSAR resist (AOE) | **Alberto Cagliani @nanotech** | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/Etching_of_Silicon_Oxide/SiO2_etch_using_AOE#Etching_with_CSAR_resist> |
| **Wordentec – Au**Temperature study of gold deposition – this is important in a lift-off process | **Kasper Reck-Nielsen and Mikkel Mar @danchip** | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Gold#Studies_of_Au_deposition_processes_in_the_Wordentec> |

# Equipment Manuals updated in LabManager:

As an approved user on a piece of equipment you have to make sure you have read and understood the latest version of the manual before using the equipment.

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| **Manual PVD co-sputter/evaporation** |
| **Manual for PL-mapper****Manual for ellipsometer M-2000V** |  |

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